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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 09/026,042
Priority Filing Date February 19, 1998
Inventor Sujit Sharan et al.
Assignee Micron Technology, Inc. and Applied Materials, Inc.
Priority Group Art Unit 1763
Priority Examiner P. Hassanzadeh, Ph.D.
Attorney's Docket No. MI22-1902
Title: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and
Methods of Effecting Plasma Enhanced Chemical Vapor Deposition

PRELIMINARY AMENDMENT

To: Assistant Commissioner for Patents
Washington, D.C. 20231

From: Frederick M. Fliegel, Ph.D.
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Sir:

This is a preliminary amendment accompanying a Request for Divisional Application for the above-entitled patent application. Prior to examining the application, please enter the following amendments.

AMENDMENTS